

b) Amendments to the Specification

Please substitute the paragraph beginning at page 43, line 7 and ending at page 44, line 18 with the following replacement paragraph which is marked-up to show changes via strikethrough or underlining:

C<sup>1</sup>

--Particularly, as shown in Fig. 1, in the inside of the film-forming vessel 101, the conductive substrate 102 is held on a substrate holder 103, and the conductive substrate 102 is electrically earthed together with the film-forming vessel 101. Reference numeral 104 indicates a heater 104 which is provided in the substrate holder 103. The substrate 102 can be heated to and maintained at a prescribed temperature by means of the heater 104 upon film formation. The discharge electrode 105 is provided at a position to oppose the substrate 102 in the film-forming vessel 101. Reference numeral 106 indicates a guard electrode which is provided at the discharge electrode 105. Reference numeral 107 indicates a high frequency power source which is connected to the discharge electrode 105 through a matching circuit 108 and a block condenser 109. Reference numeral 119 indicates a high frequency signal generator which is connected to the high frequency power source 107. Reference numeral 111 indicates a power amplifier [comprising a high speed power amplifier 4055 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the auxiliary electrode 110. Reference numeral 112 indicates a high frequency signal generator [comprising a multifunction synthesizer wave factory 1952 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the power amplifier 111. Reference numeral 113 indicates an oscilloscope which is connected to the auxiliary electrode 110. The oscilloscope 113 is used for measuring a surface potential of the auxiliary electrode 110. The film-forming vessel 101 is provided with a raw material

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gas introduction pipe 115 which is extending from a raw material gas supply system 114 comprising a plurality of reservoirs each containing a desired raw material gas therein. The film-forming vessel 101 is also provided with an exhaust pipe 117 which is connected to an exhaustion device 116 comprising a vacuum pump. Reference numeral 118 indicates a throttle valve which is provided at the exhaust pipe 117.

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Please substitute the paragraph beginning at page 47, line 17 and ending at page 49, line 3, with the following replacement paragraph marked-up to show changes therein.

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C2  
--Particularly, as shown in Fig. 14, the film-forming vessel 101 is electrically earthed. A heater 104 is provided in the substrate holder 103 so that the substrate 102 held on the substrate holder 103 can be heated to and maintained at a prescribed temperature by means of the heater 104 upon film formation. The auxiliary electrode 110 is arranged between the heater 104 and the substrate 102. Reference numeral 105 indicates a discharge electrode shaped in a plate form which is provided at a position to oppose the substrate 102 in the film-forming chamber 101. Reference numeral 106 indicates a guard electrode which is provided at the discharge electrode 105. Reference numeral 107 indicates a high frequency power source which is connected to the discharge electrode 105 through a matching circuit 108 and a block condenser 109. Reference numeral 119 indicates a high frequency signal generator which is connected to the high frequency power source 107. Reference numeral 111 indicates a power amplifier [comprising a high speed power amplifier 4055 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the auxiliary electrode 110. Reference numeral

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cont.

112 indicates a high frequency signal generator [comprising a multifunction synthesizer wave factory 1952 (produced by NF CIRCUIT DESIGN BLOCK Company)] which is connected to the power amplifier 111. Reference numeral 113 indicates an oscilloscope which is connected to the auxiliary electrode 110. The oscilloscope 113 is used for measuring a surface potential of the auxiliary electrode 110. The film-forming vessel 101 is provided with a raw material gas introduction pipe 115 which is extending from a raw material gas supply system 114 comprising a plurality of reservoirs each containing a desired raw material gas therein. The film-forming vessel 101 is also provided with an exhaust pipe 117 which is connected to an exhaustion device 116 comprising a vacuum pump. Reference numeral 118 indicates a throttle valve which is provided at the exhaust pipe 117.--

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